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Early example of an interdisciplinary approach in industry: Harold F. Winters's contributions

Eric Kay, and John W. Coburn

Journal of Vacuum Science & Technology A: Vacuum, Surfaces, and Films **35**, 05C101 (2017); <https://doi.org/10.1116/1.4989563>

Special Issue for Harold Winters Tribute Review Articles

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Review Article: Dynamics of methane dissociation on transition metals

Alan C. Luntz, and Rainer D. Beck

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Vincent M. Donnelly

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Review Article: Plasma–surface interactions at the atomic scale for patterning metals

Nicholas D. Altieri, Jack Kun-Chieh Chen, Luke Minardi, and Jane P. Chang

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Review Article: Tracing the recorded history of thin-film sputter deposition: From the 1800s to 2017

J. E. Greene

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Role of neutral transport in aspect ratio dependent plasma etching of three-dimensional features

Chad M. Huard, Yiting Zhang, Saravanapriyan Sriraman, Alex Paterson, and Mark J. Kushner

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Predicting synergy in atomic layer etching

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Energy partitioning and its influence on surface scatter coefficients within fluorinated inductively coupled plasmas

Angela R. Hanna, Michael F. Cuddy, and Ellen R. Fisher

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Effects of phosphorus and alkyl substituents on C–H, C–C, and C–O bond rupture within carboxylic acids on Ru(0001)

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Quasiatomic layer etching of silicon nitride with independent control of directionality and selectivity

Sonam D. Sherpa, Peter L. G. Ventzek, and Alok Ranjan

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Brian P. Downey, D. Scott Katzer, Neeraj Nepal, Matthew T. Hardy, and David J. Meyer

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Pingshan Luan, Andrew J. Knoll, Peter J. Bruggeman, and Gottlieb S. Oehrlein

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Achim von Keudell, and Carles Corbella

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